

Photo Mask, Computer-Aided Design (CAD) and Data Conversion Requirements

ATP has six Electro-Mask/T.R.E./ASET, two of which are Criss Cross Systems with Pattern Generators and Image Repeaters. Each system is fully self-contained in a class 100 environmentally controlled chamber. ATP is the only manufacturer in the United States that offers this combination of in-house mask making and substrate manufacturing.

In order to guarantee the highest quality circuits, ATP generates hard surface Photomasks produced on Precision Pattern Generated Equipment. ATP's masks are all fabricated to precise tolerances, whether they are for engineering or manufacturing requirements. While Mylar or Emulsion films can be used to make thin-film circuits, they can often compromise the results. ATP has extensively invested in this capability to allow us to quickly and cost-effectively produce high quality glass masks to meet our customers' needs.

Quick turn and pizza array (multi-part) engineering photomasks available.



Pattern Generator/Stepper



ATP can generate Photomasks from the following formats:

- AutoCAD .DWG or .DXF files
- Gerber photo plotter data
- GDSII files
- Dimensioned drawings
- Electromask data
- Rubylith artwork
- SolidWorks

ATP has a talented team of CAD professionals who will convert all of your formats.

Our CAD professionals are willing to lay out all of your engineering and prototype arrays. This will allow you to spend more time on designs, not the layouts.

ATP routinely produces images in Chrome and Iron Oxide on high-quality soda lime glass. In addition, we have expertise in imaging on Photographic Emulsion.

If you have an internal lab, let ATP create masks for you.

We commonly stock 3"x3" (76.2mm x 76.2mm), 4"x4" (101.6mm x 101.6mm), 5"x5" (127.0mm x 127.0mm), 6"x6" (152.4mm x 152.4mm) and 8"x8" (203.2mm x 203.2mm) Soda Lime Glass.



CAD Services